Deposit doped Poly1 layer

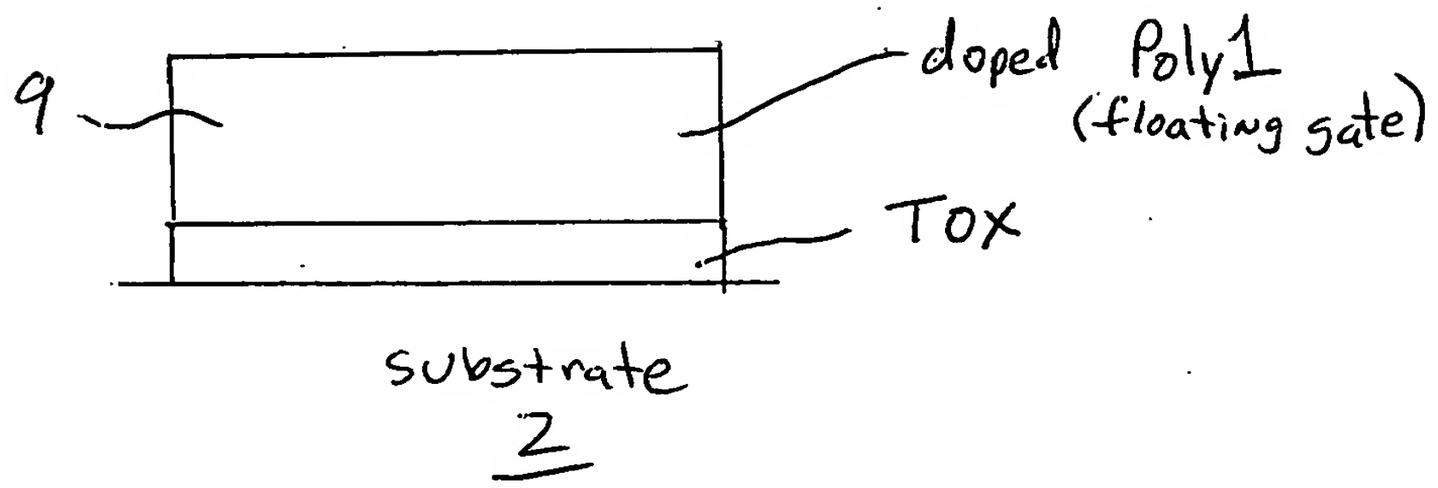

Figure 1A
(prior Art)

after thermal processes have been performed

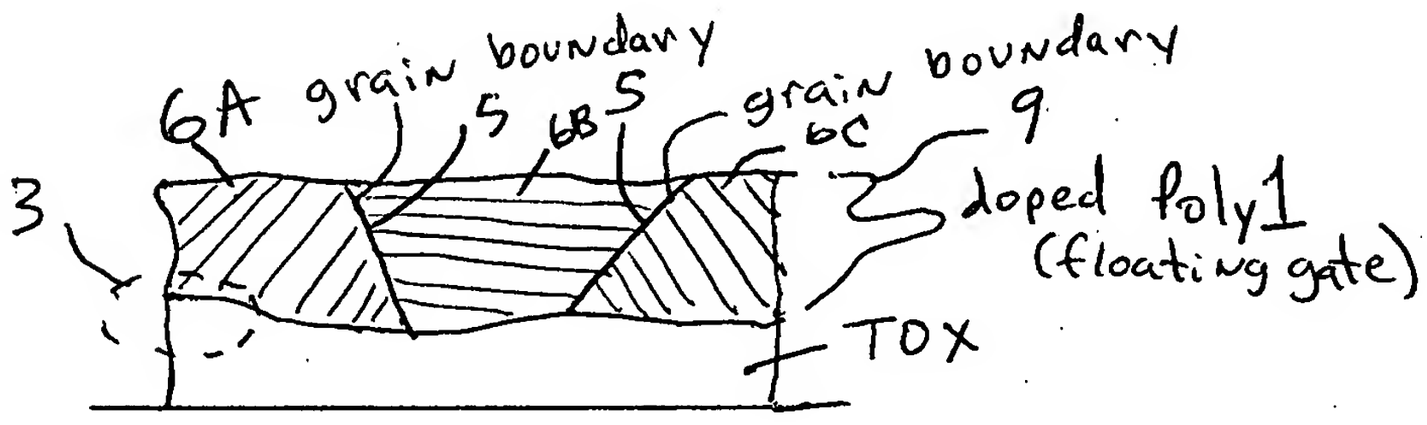

Figure 1B
(Prior Art)

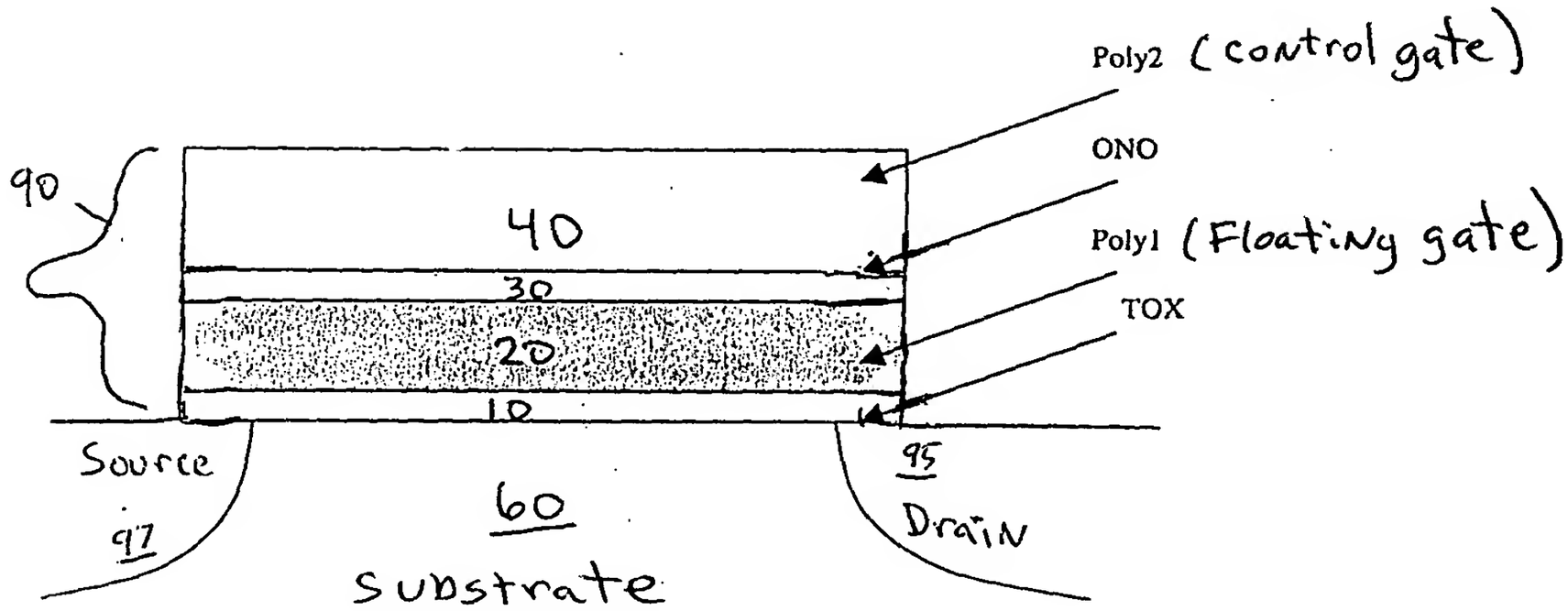
200
Poly2 (control gate)
ONO
Poly1 (Floating gate)
TOX
90
40
30
20
10
Source
97
95
Drain
60
substrate

Figure 2

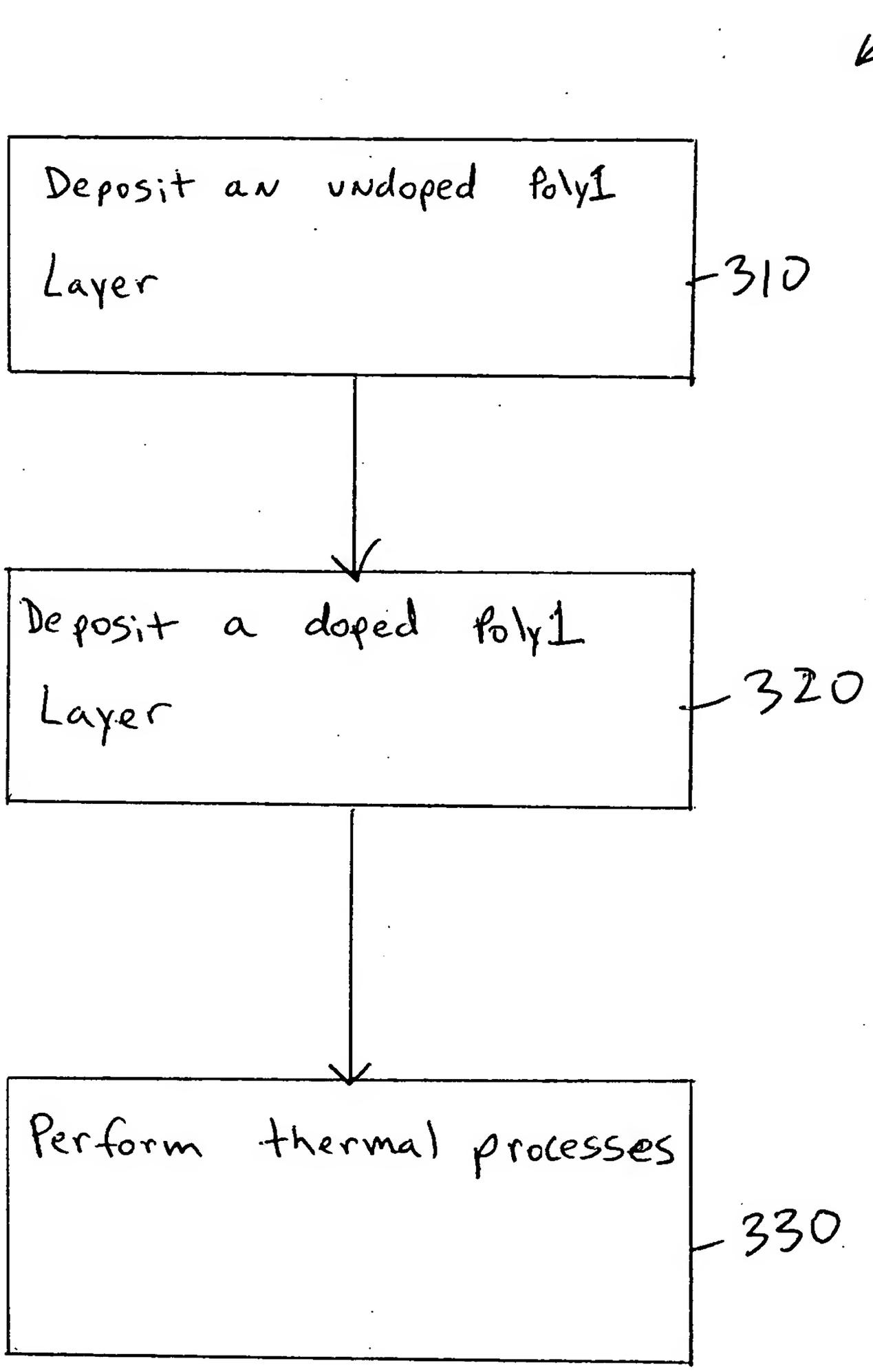
300
Deposit an undoped poly1 Layer
310
Deposit a doped poly1 Layer
320
Perform thermal processes
330

Figure 3

Deposit Undoped poly1 layer ↙200

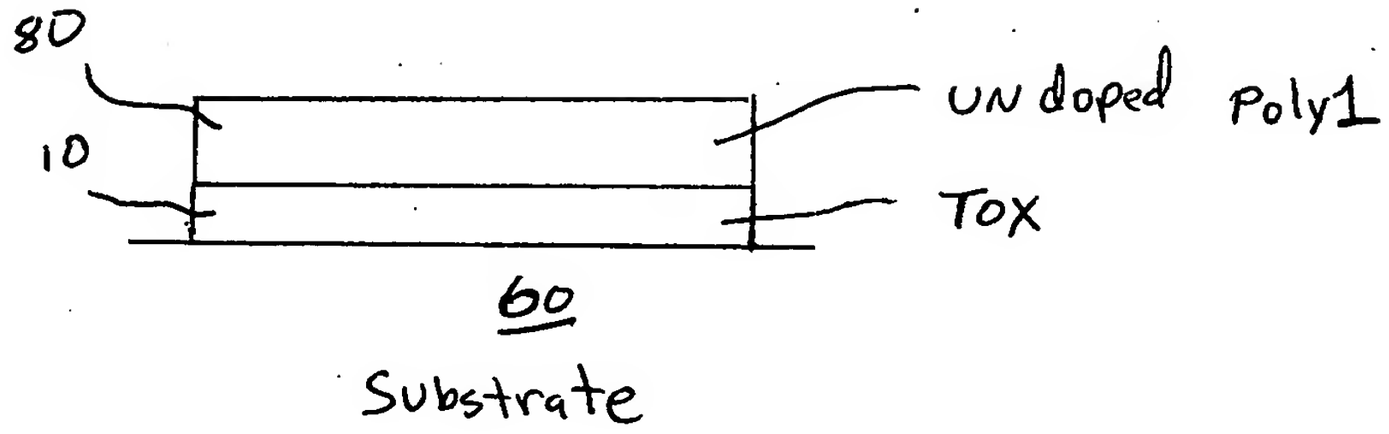

Figure 4A

Deposit doped Poly1 Layer

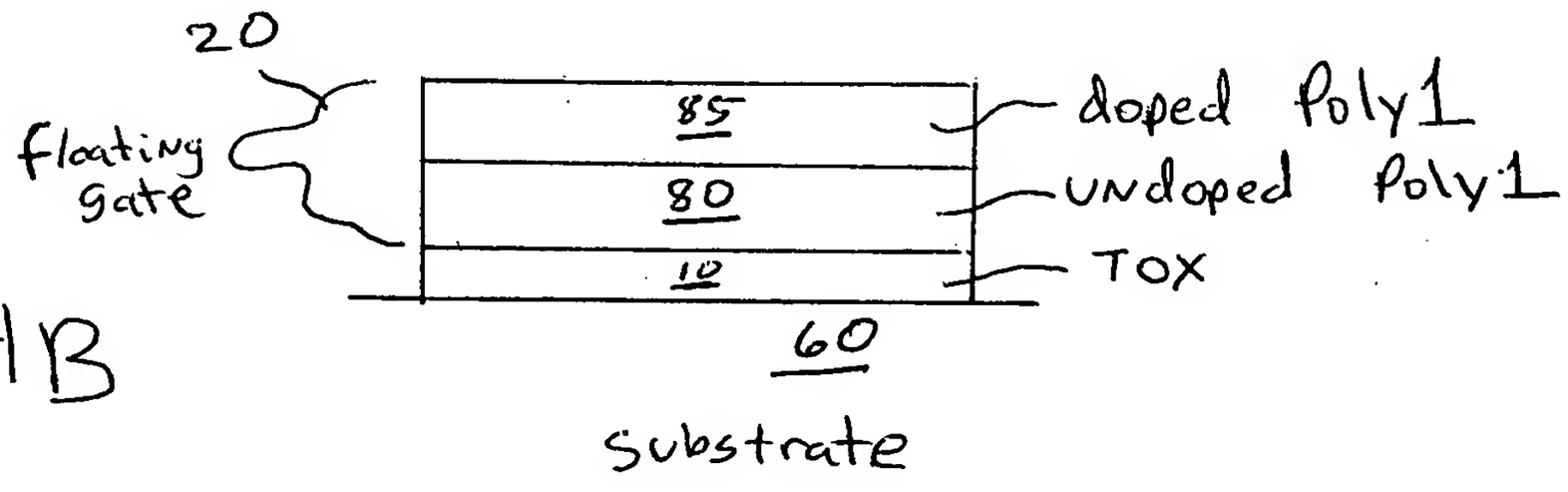

Figure 4B

After thermal processes have been performed ↙200

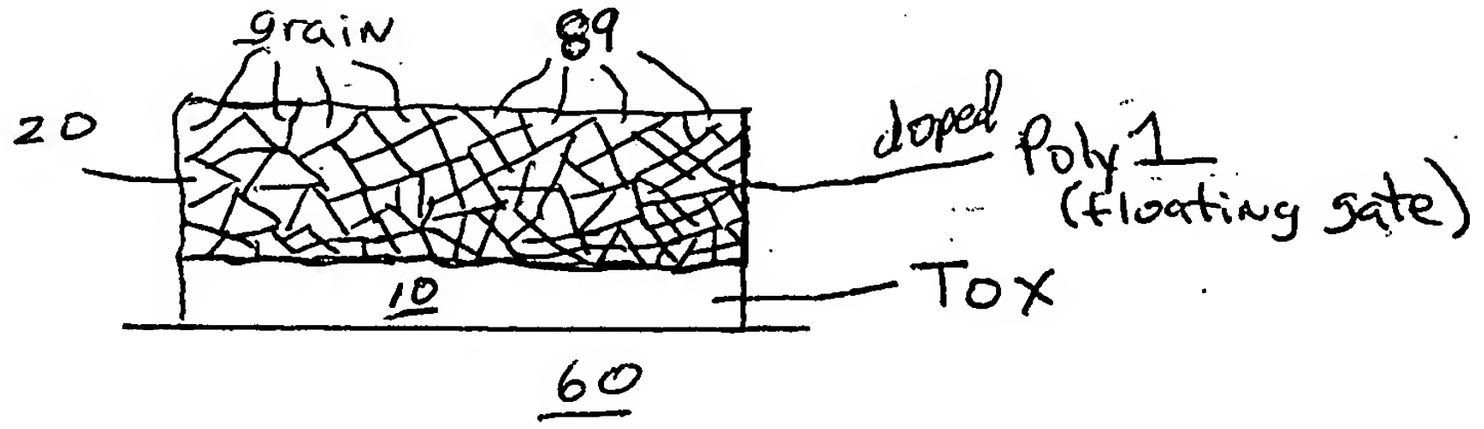

Figure 4C